

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	12028 2	355/\$.ccls. 430/\$.ccls. 356/\$.ccls.	USPAT; US-PGPUB
2	BRS	L2	5566	1 and photolithography	USPAT; US-PGPUB
3	BRS	L3	363	2 and (aberration same optic\$2)	USPAT; US-PGPUB
4	BRS	L4	99	3 and (measur\$4 same aberration)	USPAT; US-PGPUB
5	BRS	L5	86	4 and (reticle mask) and (wafer or substrate) and pattern	USPAT; US-PGPUB
6	BRS	L6	61	5 and (projected with (pattern image))	USPAT; US-PGPUB
7	BRS	L7	50	6 and (difference\$2 deviation\$2)	USPAT; US-PGPUB
8	BRS	L8	23	7 and spac\$4 and feature\$2	USPAT; US-PGPUB
9	BRS	L9	9	8 and ccd	USPAT; US-PGPUB
10	BRS	L10	8	9 and interference	USPAT; US-PGPUB
11	BRS	L11	1	9 not 10	USPAT; US-PGPUB
12	BRS	L12	14	8 not 9	USPAT; US-PGPUB

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